

<b>Notice of References Cited</b>	Application/Control No. 10/725,139		Applicant(s)/Patent Under Reexamination SATO ET AL.	
	Examiner Elias Desta		Art Unit 2857	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,924,455	08-2005	Chen et al.	219/121.41
*	B	US-2005/0173376	08-2005	Donohoe, Kevin G.	216/067
	C	US-			
	D	US-			
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	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Frederico et al., 'Silicon Sacrificial Layer Dry Etching (SSLDE) for Free-standing RF MEMS Architectures', January 2003, IEEE Publication, pages 570-573
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.